

DIERICHS et al. — 10/784,895  
Attorney Docket: 081468-0305313

IN THE ABSTRACT:

The abstract is amended as follows:

A lithographic apparatus includes a device having a plurality blades, each blade being selectively insertable into the beam of radiation. The device is in a first plane intermediate a second plane conjugate to a plane of the substrate and a third plane conjugate to a pupil plane of the projection system. The blades ~~[[may]]~~ include a plurality of partially opaque and solid blades or ~~a plurality of blades having~~ have a predetermined transmissibility pattern. The transmissibility may vary in a second direction perpendicular to the first direction in which the substrate and the patterning device are movable ~~relative to each other~~. In an illumination system including a field faceted mirror and a pupil faceted mirror, ~~the illumination system may include~~ a plurality of reflecting blades are selectively insertable into the beam to reflect a portion of the beam to a beam dump. ~~The beam dump that~~ that may be cooled to reduce a heat load ~~on the apparatus~~. The reflecting elements may ~~be coated with~~ have a coating that scatters the portion of radiation or changes the phase ~~of the portion of radiation~~.